



FORM PTO-1449 (MODIFIED)

JUN 19 2002

LIST OF PATENTS AND
PUBLICATIONS
FOR APPLICANTS INFORMATION
DISCLOSURE STATEMENT

ATTORNEY DOCKET NO.

SP01-330

SERIAL NO.

10/086,238

APPLICANT Bowden et al.

FILING DATE February 27, 2002

GROUP: 1731

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TC 1700

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
<i>JHP</i>	AA	2,326,058	8/3/43	Nordberg <i>Nadeau</i>	100	52	
	AB	4,501,602	2/26/85	Miller et al.	65	18.2	
	AC	5,043,002	8/27/91	Dobbins et al.	65	3.12	
	AD	5,152,819	10/6/92	Blackwell et al.	65	3.12	
	AE	5,154,744	10/13/92	Blackwell et al.	65	3.12	
	AF	5,686,728	11/11/97	Shafer	250	492.2	
	AG	5,970,751	10/26/99	Maxon et al.	65	414	
<i>JHP</i>	AH	6,013,399	1/11/00	Nguyen	430	5	
	AI	6,299,318	10/9/01	Braat	359	856	

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Sub-Class	Translation Yes No
<i>JHP</i>	AJ	WO 01/07967 ·	2/1/01	PCT	G03C	5/00	X
	AK	WO 01/08163 ·	2/1/01	PCT	G21K	5/00	X
	AL	WO 01/75522 ·	10/11/01	PCT	G03F	1/14	X
	AM	WO 00/48775 ·	8/24/00	PCT	B23B	—	X
	AN	WO 02/32622 ·	4/25/02	PCT	B24B	7/24	X
	AO	WO 02/26647 ·	4/4/02	PCT	C03B	37/016	X
	AP	WO 02/32616 ·	4/25/02	PCT	B23P	13/04	
<i>JHP</i>	AQ	EP 0 903 605A2	3/24/99	EPO	G02B	13/14	X
	AR	EP 1 106 582A2	6/13/01	EPO	C03B	19/10	X

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OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

	A1	P. Shultz & H. Smith, Ultra-Low-Expansion Glasses and Their Structure in the SiO ₂ -TiO ₂ System, Amorphous Materials, papers presented to the Third International Conference on the Physics of Non-Crystalline Solids, held at Sheffield University, September 1970
	A2	George H. Beall, Industrial Applications of Silica, Reviews in Mineralogy, Vol. 29 (Silica), (1994), 469-505.
	A3	Charles Gwyn et al., Extreme Ultraviolet Lithography, November 1999, 97-141.
	A4	EUV Lithography NGL Technology Review, June 9, 1999, Chicago, Illinois.
	A5	Charles Gwyn et al., Extreme Ultraviolet Lithography, 1-6.
	A6	William M. Tong et al., Substrates Requirements For Extreme Ultraviolet Lithography, Information Science & Technology, Lawrence Livermore National Laboratory, December 1999.
	A7	O.V. Mazurin et al., Crystallization of Silica and Titanium Oxide-Silica Corning Glasses (Codes 7940 & 7971), Journal of Non-Crystalline Solids 18, (1975) 1-9.
	A8	ISIMOTO CO. LTD., Purity and Chemical Reactivity, http://www.isimoto.com/isimoto/english/feature1.html , 1-3, 5/17/99
	A9	ISIMOTO CO. LTD., Product Information, http://www.isimoto.com/isimoto/english/product_info.html , 1-4, 5/17/99
	A10	Rapid Prototyping, http://mtiac.iitri.org/pubs/rp/rp1.htm
	A11	Products: SLS (R) Systems – Introduction, Vanguard™ and Vanguard™ HS, http://www.3dsystems.com/products/slsystems/vanguard/index.asp?promo=
	A12	Corning, Semiconductor Materials ULE Zero Expansion Glass, http://www.corning.com/semiconductormaterials/products_services/ule.asp
	A13	Richard H. Stulen et al., Extreme Ultraviolet Lithography, IEEE Journal of Quantum Electronics, Vol. 35, No. 5, May 1999, 694-699..

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